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**NATIONAL STANDARD OF THE
PEOPLE'S REPUBLIC OF CHINA**

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**Specification for metrology pattern cells for integrated circuit
manufacture**

(English Translation)

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What this standard covers

This standard specifies several standard test patterns for micro graphics device used in the production of integrated circuits, measurement instruments and processes consistent with the comprehensive assessment and testing. The standard width for the needs of metrology, resolution test and proximity effects testing requirements for certain types of test patterns shape the basic unit, the general size, and the recommended layout and design rules. These include standard graphics available optical microscopy, electron microscopy and electron microprobe measurements with various graphic elements. This standard does not specify the measurement techniques to verify the size of the master key test pattern, nor specify how to measure the resist pattern on the wafer, the only requirements for certain kinds of necessary basic test pattern, and the user's actual implementation in line with the standard test pattern.

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